

# CHEMICAL DEPOSITION OF MORPHOLOGICALLY CONTROLLED CU20 NANOCRYSTAL FILMS AND THEIR PHOEPENDENT GALVANIC REPLACEMENT.

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Nanostructured cuprous oxide (Cu20) is an intriguing direct bandgap semiconductor material with potential applications as a UV-Vis light absorber in solar cells, a photocatalyst for the degradation of organic pollutants, a negative electrode in Li-ion batteries, and others.

It is known that the morphology and size of Cu20 nanoparticles (NPs) may affect their photocatalytic and light-absorption properties. However, the preparation of Cu<sub>2</sub>0 NPs with morphological control has been largely restricted to colloidal syntheses and electrodeposition on substrates.

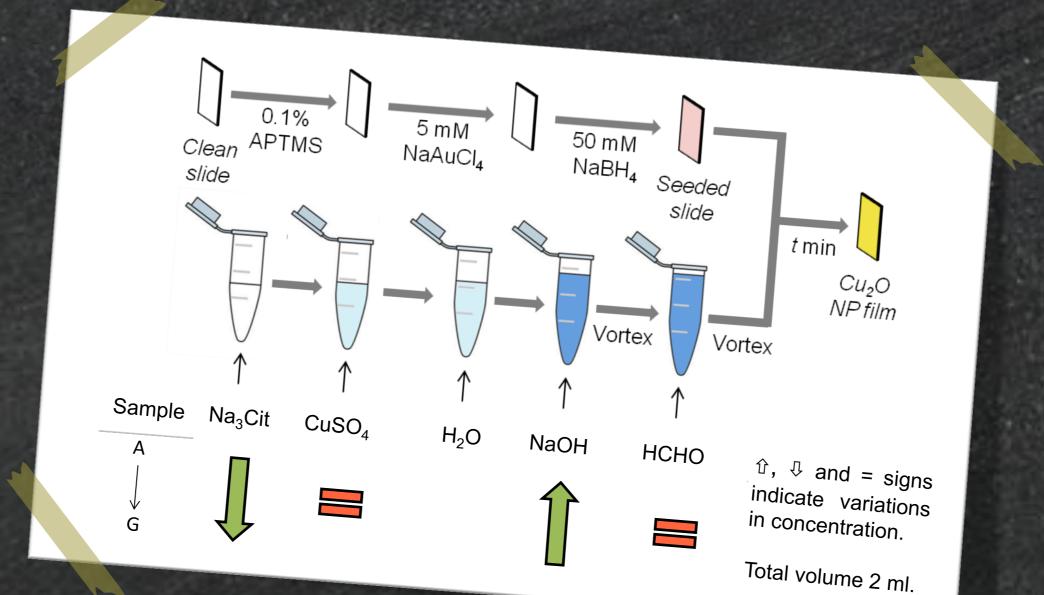
Here we present a chemical (electroless) deposition (CD) approach to direct preparation of Cu2O nanocrystal (NC) films on substrates, using CuSO4-HCHO-Citrate-NaOH solutions. Our method shows a high degree of morphology control. The average NC size can be varied by controlling the deposition time, while the crystallographic structure is determined by the solution composition. The NC films were studied by SEM, TEM, GIXRD and UV-Vis spectroscopy,

The supported Cu<sub>2</sub>0 NCs were used to study their galvanic replacement (GR) reactions with metal salts in solutions of different pH. The resulting structures of the replaced Cu<sub>2</sub>0 NPs showed high dependence on the solution's pH, producing from Cu<sub>2</sub>0 particles decorated with smaller metal (Me) NPs to supported Cu20@Me nanoarchitectures.

#### SAMPLE PREPARATION

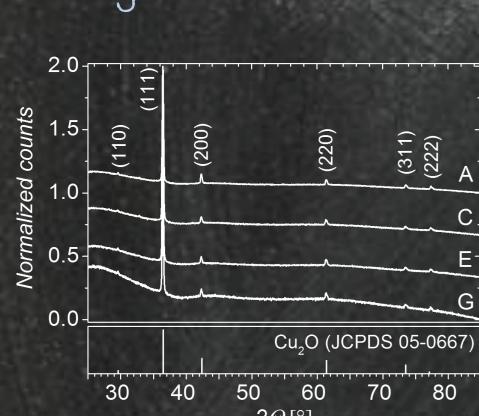
Au seeds were produced in-situ on glass or quartz slides.

Cu20 NC films were chemically deposited from formaldehyde-based solutions of different compositions (A to G), optimized for the preparation of Cu<sub>2</sub>0 NCs with precise morphology.

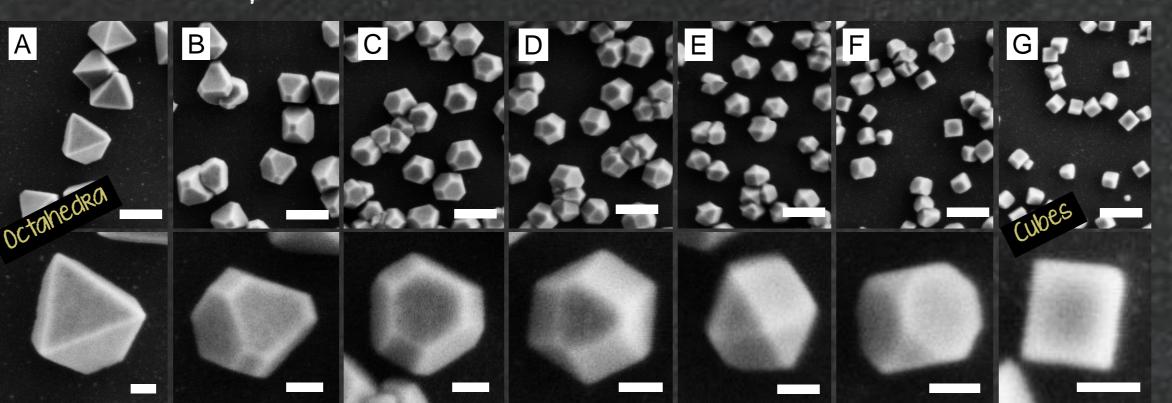


## CHARACTERIZATION

Grazing Incidence XRD

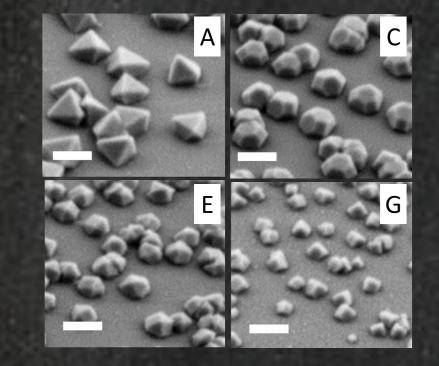


SEM images Scale bars: Top - 200 nm, bottom - 50 nm.



SAED (A)

Tilted Angle SEM (45°). Scale bars: ~200 nm.



UV-Vis spectroscopy

TEM images (Cu<sub>2</sub>0 NCs prepared after seeding of carbon-coated grids). Scale bars: A - 100 nm, G - 50 nm. Corresponding SAED patterns from octahedra are shown.

NCs viewed along the indicated directions. Scale bars: A,C,E - 100 nm, G - 50 nm.

[100] [110] [111]

HRSEM (After 3 nm Cr sputtering).

Dissolution of the Cu<sub>2</sub>O cores

GALVANIC REPLACEMENT (GR)

ESB

Pd(II)

ESB

CONCLUSIONS

the deposition time.

conditions.

Treatment of Cu20 NCs with 0.5 mM MeCl4n-

solutions lead to the formation of metal (Me)

depend on the solution pH. Scale bars: 100 nm.

 $3/2 \text{ Cu}_20 + \text{AuCl}_{4^-} + 3 \text{ H}^+ \rightarrow \text{Au}^0 + 3 \text{ Cu}^{2+} + 3/2 \text{ H}_20 + 4 \text{ Cl}$ 

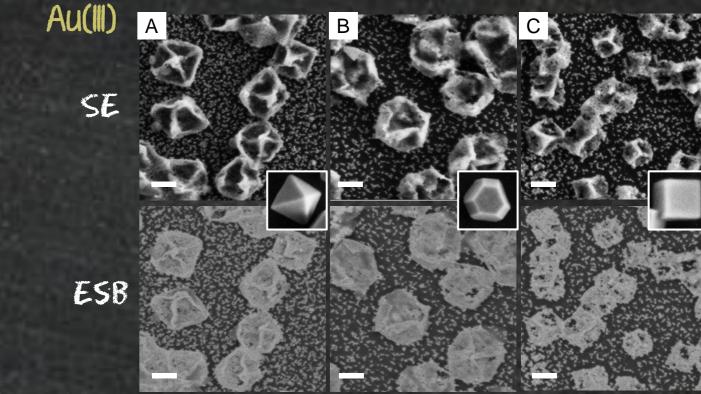
 $Cu_2O + PdCl_4^{2-} + 2H^+ \rightarrow Pd^0 + 2Cu^{2+} + H_2O + 4Cl_4^{2-}$ 

Lower pHs promote uniform metal (Me)

nucleation on the Cu<sub>2</sub>O NC surface.

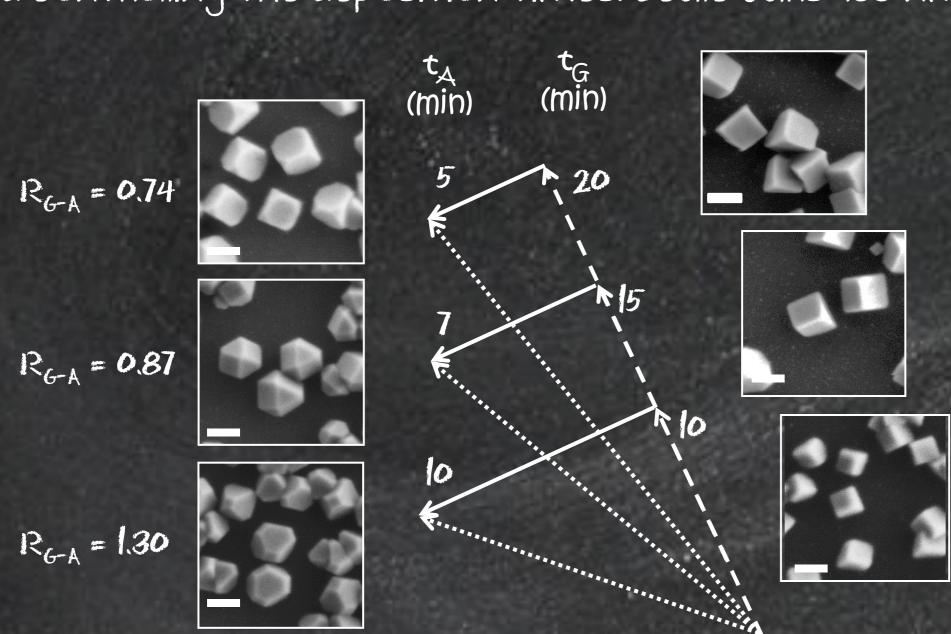
layers on the Cu<sub>2</sub>O NPs, with structures that

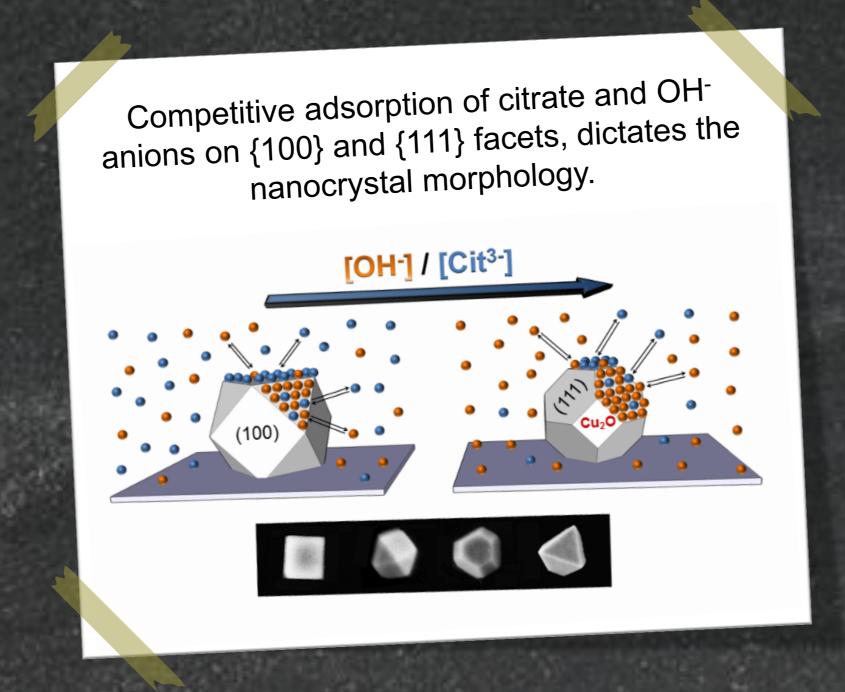
Cores of Cu20@Au NPs were dissolved in 10 mM HCl to reveal the NP surface structure. Scale bars: 100 nm.



### SEQUENTIAL DEPOSITION

Morphological and size control can also be achieved by sequential immersion of the slides in solutions A and G, and controlling the deposition times. Scale bars: 100 nm.





t = 10 min

### 2) The Cu<sub>2</sub>0 NC morphology can be shifted by sequential immersions in different growth media (e.g., solutions A and G).

1) Cu20 NC films with precisely controlled morphology

can be prepared by CD. The morphology is determined

by competitive adsorption of citrate and OH- on {100}

and {111} facets. The average NC size is determined by

3) NPs are truncated on the substrate side and strongly adhere to it (pass the Scotch tape test). 4) Structures obtained by GR reactions of Cu20 NCs with metal salts are highly dependent on the solution pH. Metal-decorated Cu20 NPs, Cu20@Me, and metal

nanocages, can be produced under appropriate

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Susman, M. D.; Feldman, I.; Vaskevich, A.; Rubinstein, I., *Chem. Mater*. 2012, 24(13), 2501-2508. <sup>2</sup> Susman, M. D.; Feldman, I.; Vaskevich, A.; Rubinstein, I., - *Submitted*.